IAP15 Rec'd PCT/PTO 19 OCT 2006

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FORM PTO-1390 US DEPARTMENT OF COMMERCE PATENT & TRADEMARK OFFICE ATTORNEY'S DOCKET NUMBER (REV. 01-2003) 128375 TRANSMITTAL LETTER TO THE UNITED STATES U.S. APPLICATION NO. (If known, see 37 CFR 1.5) 10/582,268 DESIGNATED/ELECTED OFFICE (DO/EO/US) **CONCERNING A FILING UNDER 35 U.S.C. 371** INTERNATIONAL APPLICATION NO. INTERNATIONAL FILING DATE PRIORITY DATE CLAIMED PCT/JP2004/018702 December 15, 2003 December 15, 2004 TITLE OF INVENTION STAGE APPARATUS, EXPOSURE APPARATUS, AND EXPOSURE METHOD APPLICANT(S) FOR DO/EO/US Yasufumi NISHII; Kenichi SHIRAISHI; Hirotaka KOHNO Applicant herewith submits to the United States Designated/Elected Office (DO/EO/US) the following items and other information: This is a FIRST submission of items concerning a filing under 35 U.S.C. 371. 1. 2. This is a SECOND or SUBSEQUENT submission of items concerning a filing under 35 U.S.C. 371. 3. This is an express request to begin national examination procedures (35 U.S.C. 371(f)). The submission must include items (5), (6), (9) and (21) indicated below. 4. The US has been elected (Article 31). 5. A copy of the International Application as filed (35 U.S.C. 371(c)(2)) a. \square is attached hereto (required only if not communicated by the International Bureau). b. has been communicated by the International Bureau. c. I is not required, as the application was filed in the United States Receiving Office (RO/US). An English language translation of the International Application as filed (35 U.S.C. 371(c)(2)) 6. b. has been previously submitted under 35 U.S.C. 154(d)(4). The International Application was filed in English. Amendments to the claims of the International Application under PCT Article 19 (35 U.S.C. 371(c)(3)) 7. a. \square are attached hereto (required only if not communicated by the International Bureau). b. In have been communicated by the International Bureau. c. have not been made; however, the time limit for making such amendments has NOT expired. An English language translation of the amendments to the claims under PCT Article 19 (35 U.S.C. 371(c)(3)). 8. 9. An oath or declaration of the inventor(s) (35 U.S.C. 371(c)(4)). 10. An English language translation of the annexes of the International Preliminary Examination Report under PCT Article 36 (35 U.S.C. 371(c)(5)). Items 11 to 20 below concern document(s) or information included: 11. An Information Disclosure Statement under 37 CFR 1.97 and 1.98. An assignment document for recording. A separate cover sheet in compliance with 37 CFR 3.28 and 3.31 is included. 12. 13. П A preliminary amendment. 14. An Application Data Sheet under 37 CFR 1.76. 15 A substitute specification. П 16. A power of attorney and/or change of address letter. 17 A computer-readable form of the sequence listing in accordance with PCT Rule 13ter.2 and 37 CFR 1.821 - 1.825. П 18. A second copy of the published international application under 35 U.S.C. 154(d)(4). 19. A second copy of the English language translation of the international application under 35 U.S.C. 154(d)(4). 20. Other items or information:

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PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Yasufumi NISHII et al.

Application No.: 10/582,268

Filed: June 9, 2006 Docket No.: 128375

For: STAGE APPARATUS, EXPOSURE APPARATUS, AND EXPOSURE METHOD

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- 2. In accordance with 37 CFR §1.98(a)(2)(ii), copies of any U.S. patents and patent application publications are not attached.
- 3. An English language Abstract of one or more non-English language reference is attached hereto. See References 121 135.
- 4. A computer-generated English language translation of one or more Japanese Patent Publication cited herein has been obtained from the website of the Japanese Patent Office ([http://www.jpo.go.jp]), and is attached, but has not been reviewed for accuracy. See Reference 135.

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5. Non-computer-generated English language translations of references <u>121 - 134</u> are attached hereto, but have not been reviewed for accuracy.

Respectfully submitted,

Mario A. Costantino Registration No. 33,565

Randi B. Isaacs Registration No. 56,046

MAC:RBI/kam

Date: October 19, 2006

OLIFF & BERRIDGE, PLC P.O. Box 19928 Alexandria, Virginia 22320 Telephone: (703) 836-6400 DEPOSIT ACCOUNT USE
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INFORMATION DISCLOSURE STATEMENT

(Use several sheets if necessary)

APPLICANT(S)
Yasufumi NISHII et al.

FILING DATE
June 9, 2006

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